<u> </u>			
Notice of Allowability	Application No.	Applicant(s)	
	09/854,760	NING, XIAN J.	
	Examiner	Art Unit	
	Lan Vinh	1765	
Th MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in the commod of the c	n this application. If not included unication will be mailed in due course.	
1. This communication is responsive to <u>Amendment filed on</u>	<u>8/26/2003</u> .		
2.  The allowed claim(s) is/are 1-13 and 22-24.	•		
<ul> <li>3.</li></ul>		or (f).	
1.   Certified copies of the priority documents have	e been received.		
2.  Certified copies of the priority documents have	e been received in Application	on No	
<ol><li>Copies of the certified copies of the priority de</li></ol>	ocuments have been receive	d in this national stage application from	m the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:  5. ☑ Acknowledgment is made of a claim for domestic priority or reference was included in the first sentence of the specific (a) ☐ The translation of the foreign language provisional  6. ☐ Acknowledgment is made of a claim for domestic priority or in the first sentence of the specification or in an Application	cation or in an Application Date application has been receive under 35 U.S.C. §§ 120 and/	ta Sheet. 37 CFR 1.78. d.	
Applicant has THREE MONTHS FROM THE "MAILING DATE" of below. Failure to timely comply will result in ABANDONMENT or	of this communication to file a	a reply complying with the requirement REE-MONTH PERIOD IS NOT EXTEN	ts noted
7. A SUBSTITUTE OATH OR DECLARATION must be subr INFORMAL PATENT APPLICATION (PTO-152) which give	nitted. Note the attached EX ves reason(s) why the oath o	AMINER'S AMENDMENT or NOTICE r declaration is deficient.	OF
<ol> <li>CORRECTED DRAWINGS (as "replacement sheets") mu</li> <li>(a) ☐ including changes required by the Notice of Draftsper</li> <li>1) ☐ hereto or 2) ☐ to Paper No</li> </ol>		w(PTO-948) attached	
(b) $\ \square$ including changes required by the proposed drawing			
(c) ☐ including changes required by the attached Examiner	's Amendment / Comment o	r in the Office action of Paper No	<u>.                                    </u>
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on t the margin according to 37 Cl	he drawings in the front (not the back) o R 1.121(d).	of
<ol> <li>DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT FOR</li> </ol>	osit of BIOLOGICAL MAT THE DEPOSIT OF BIOLOGI	ERIAL must be submitted. Note the CAL MATERIAL.	)
Attachment(s)		,	
1☐ Notice of References Cited (PTO-892)	5∐ Notice of Inf	ormal Patent Application (PTO-152)	
2 Notice of Draftperson's Patent Drawing Review (PTO-948)		mmary (PTO-413), Paper No	
3 Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No	8), 7□ Examiner's A	Amendment/Comment	
4☐ Examiner's Comment Regarding Requirement for Deposit	8⊠ Examiner's S	Statement of Reasons for Allowance	
of Biological Material	9 <b>□</b> Other		
		Lan Vinh AU 1765	

U.S. Patent and Trademark Office PTOL-37 (Rev. 11-03) Application/Control Number: 09/854,760

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## Allowable Subject Matter

1. Claims 1-13, 22-24 are allowed.

The following is an examiner's statement of reasons for allowance:

Regarding claim 1, the cited prior art of record fails to disclose a method for producing a semiconductor device having an alignment mark comprises the step of patterning a second resist layer (the second resist layer is deposited over an etched second dielectric layer) to define a second multiplicity of apertures. The closest cited prior art of Sung et al (US 6,346,454) discloses a method for making dual damascene comprises the step of forming a second resist layer 62 over an etched second dielectric layer 42 and a formed second opening/ aperture 60 without performing a patterning step on the second resist layer to define a second multiplicity of apertures (col 5, lines 65-67; col 6, lines 12-15, fig. 5)

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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## Conclusion

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lan Vinh whose telephone number is 703 305-6302. The examiner can normally be reached on M-F 8:30-5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 703 305-2667. The fax phone number for the organization where this application or proceeding is assigned is 703 872-9310.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703 308-0661.

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November 28, 2003

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